



Recent Developments and Signal Processing of Low Driving Voltage and High Modulation Efficiency Electro-absorption Modulators (EAMs)

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ABSTRACT

Electro-absorption (EA) modulators are very attractive devices for optical fiber communications because of their very low driving voltage, very high modulation efficiency and integrability with lasers. However, conventional EA modulators are lumped electrode devices, whose speeds are limited by the total parasitics of the devices, which restricts the devices to very short length for high speed operation. This paper has presented the important transmission characteristics of EA modulators such as transmission performance efficiency, modulation photocurrent, insertion loss, extinction ratio, relative refractive index difference, and signal transmission quality, over wide range of the affecting parameters for different selected electro-absorption materials to be the major of interest.

Keywords: Low Driving Voltage, High Modulation Efficiency, Low Chirp, Reverse Bias Voltage, Speed Response

1. INTRODUCTION

The transmission bit rates in backbone telecommunication optical fibers are increasing rapidly, motivated by the explosive growth of Internet traffic. As the channel bit rate distance product increases, external modulation of the laser light is necessary to avoid the unacceptably high chirping of directly modulated lasers and to overcome the dispersion of standard single mode fiber [1]. LiNbO₃ electro-optic modulators are currently widely used in low bit-rate applications. However, the high drive voltage requirement for these modulators becomes a big problem at high bit rates. On the other hand, Electro-Absorption (EA) modulators based on quantum confined Stark effect in Multiple Quantum Wells (MQWs) are advantageous for their high speed, low drive voltage, high extinction ratio and integrability with lasers. Currently, EA modulators use lumped electrode structures, which limit the device bandwidth by the RC time constant and require a short device length for high speed operation [2].

Nonlinear optical and linear electro-optic materials find use in switching and modulation devices for photonic integrated circuits. For modulators in telecommunications small size and modulation voltages are desired. Both Electro-Absorption (EA) and Electro-Optic (EO) modulators are candidates for use in external modulation links in telecommunications. These modulators can be realized using either bulk semiconductor materials [3] or materials with

multiple quantum dots or wells. Electro-absorption modulators have been widely used in fiber optic communication systems for their small size, low driving voltage, low chirp, and high bandwidth [4]. In addition, due to matching of material systems, EAMs can be easily integrated with other optical components, such as semiconductor lasers, semiconductor optical amplifiers, and attenuators. Since many material properties, such as bandgap, refractive index, and thermal conductivity, change with temperature, internal heating must be considered in the design of an Electro-Absorption Modulator (EAM). This is especially important for high power operation, because large heating can damage the device. The input power tolerance of InGaAsP EAMs have been investigated experimentally in terms of breakdown phenomena, and it was shown that optical power for breakdown depended on bias voltage and operating wavelength [5]. In addition, since incident light is attenuated along the modulator, the temperature distribution is not uniform, as measured by [6], using a liquid crystal technique. The positive feedback from the interaction of absorption and temperature may make light absorption and heating greatly localized at the input of the modulator, and the peak temperature increased nonlinearly with incident light power and bias voltage.

EAMs are among the most important components of high speed Wavelength Division Multiplexing (WDM) optical communications devices and systems. EAMs are widely used as stand alone devices, as part of electro-absorption modulated lasers, and as part of multi-component planar lightwave circuits. Since the first proposed EAMs based on optical absorption of light in a bulk structure more than two decades ago [7], advances have been made in modulator performances such as extinction ratio, polarization insensitivity, and bandwidth. MQWs structures in the active region have become the structures of choice for EAMs due to their improved extinction and reduced polarization sensitivity through applied strain [8]. While lumped electrode devices have demonstrated performance at rates of 10 Gb/s and higher, the more recent traveling wave electrode devices have been shown to work at rates of 43 Gb/s and above [9]. Compared to the other popular class of modulators, Mach Zehnder based Lithium Niobate modulators, EAMs offer a number of advantages such as low voltage drive, small size, high bandwidth, and potential for monolithic integration with other optoelectronic devices.

For good performance of the modulator, a high extinction ratio is necessary.

In the present study, EAMs are typically electrically driven to vary the electric field across the device and hence the optical transmission through it. Waveguide EAMs are increasingly being used in optical networks since they can be monolithically integrated with continuous wave edge emitting laser diodes to create low cost, high speed optical transmitters. The high speed transmission characteristics of electro-absorption modulators under wide range of the affecting parameters are investigated. The maximum modulation bandwidth is deeply analyzed. The theoretical modulation response of the EAM is derived from the standard rate equations, and the qualitative form is in agreement with the measured results.

2. THEORETICAL MODEL ANALYSIS

The investigation of both the thermal and spectral variations of the electrooptic (EO) modulator effective refractive index (n_e) require Sellmeier equation. The set of parameters required to completely characterize the temperature dependence of the refractive-index is given below, Sellmeier equation is under the form [10][11]:

$$n_e = \sqrt{1 + \frac{A_1 \lambda^2}{\lambda^2 - A_2^2} + \frac{A_4 \lambda^2}{\lambda^2 - A_4^2} + \frac{A_5 \lambda^2}{\lambda^2 - A_6^2}} \quad (1)$$

For different selected semiconductor electro-optic materials based EOMs, where the Sellmeier coefficients for Silicon (Si), Germanium (Ge), and arsenic trisulfide (AS₂S₃) are listed in the following Table 1.

Table 1: Sellmeier coefficients for different selected semiconductor EO materials [12][13][14][15]

Coefficients	Si	Ge	AS ₂ S ₃
A ₁	10.6684293 (T/T ₀)	14.7587446 (T/T ₀)	4.07205767 (T/T ₀)
A ₂	0.301516485 (T/T ₀) ²	0.434303403 (T/T ₀) ²	0.208841706 (T/T ₀) ²
A ₃	0.0030434748 (T/T ₀)	0.235256294 (T/T ₀)	0.744196974 (T/T ₀)
A ₄	1.13475115 (T/T ₀) ²	1.26245893 (T/T ₀) ²	0.3959647 (T/T ₀) ²
A ₅	1.54133408 (T/T ₀)	-24.8822748 (T/T ₀)	0.988377784 (T/T ₀)
A ₆	1104 (T/T ₀) ²	1302 (T/T ₀) ²	27.7481958 (T/T ₀) ²

Where T is the ambient temperature, and T₀ is the room temperature respectively. Then the first and second differentiation of empirical equation with respect to operating wavelength λ yields the following expressions:

$$\frac{dn_e}{d\lambda} = \frac{-1}{n_e} \left(\frac{A_1 A_2^2 \lambda}{(\lambda^2 - A_2^2)^2} + \frac{A_3 A_4^2 \lambda}{(\lambda^2 - A_4^2)^2} + \frac{A_5 A_6^2 \lambda}{(\lambda^2 - A_6^2)^2} \right) \quad (2)$$

$$\frac{d^2 n_e}{d\lambda^2} = \frac{1}{n_e} \left(\frac{A_1 A_2^2 (3\lambda^2 + A_2^2)}{(\lambda^2 - A_2^2)^3} + \frac{A_3 A_4^2 (3\lambda^2 + A_4^2)}{(\lambda^2 - A_4^2)^3} + \frac{A_5 A_6^2 (3\lambda^2 - A_6^2)}{(\lambda^2 - A_6^2)^3} \right) - \left(\frac{dn_e}{d\lambda} \right)^2 \quad (3)$$

The change in mode effective index varies linearly with the applied voltage, and the change in the mode effective index due to applied voltage ($\Delta n(V)$) is given in below [16][17]:

$$\Delta n_e(V) = \frac{0.5 r_{41} n_e^3 \Gamma V}{t} \quad (4)$$

Where r₄₁ is the electro-optic coefficient, t is the thickness of the modulator thickness, Γ is the confinement factor, and V is the applied bias voltage. Given the material absorption coefficient α and optical confinement of the intrinsic layer, and assuming unity quantum efficiency, the modulation photocurrent I_{mod} can be calculated for length L of modulator:

$$I_{mod} = \frac{P q \lambda (1 - \exp(-\alpha \Gamma L))}{2\pi c h} \quad (5)$$

Where c is the speed of light, h is the Planck's constant, P is the input light power, q is the electron charge, and λ is the operating optical signal wavelength. As well as the material absorption coefficient, α in μm⁻¹, which can be expressed as a function of operating optical signal wavelength by using MATLAB fitting program for different semiconductor materials based EOMs as [18][19]:

$$\alpha = 0.7721 + 0.005868 \lambda - 0.0931 \lambda^2 \quad , \text{ (Si)} \quad (6)$$

$$\alpha = 44.5643 - 0.008893 \lambda + 0.00135 \lambda^2 \quad , \text{ (Ge)} \quad (7)$$

$$\alpha = 0.2345 + 0.005143 \lambda - 0.0852 \lambda^2 \quad , \text{ (AS}_2\text{S}_3\text{)} \quad (8)$$

The transmission spectra, T_m, insertion loss, IL, and extinction ratio, ER, of the different EA modulator devices with using MATLAB curve fitting program as [20][21][22]:

$$T_m = 0.854 - 0.00297 \alpha V^{-1} + 0.0765 \alpha^2 V^{-2} - 0.0037 \alpha^3 V^{-3} \quad (9)$$

$$IR = 35.54 - 0.008 \alpha + 0.00076 \alpha^2 - 0.03 \alpha^3 \quad , \text{ dB} \quad (10)$$

$$ER = 9.76 + 0.765 \alpha V - 0.00043 \alpha^2 V^2 + 0.054 \alpha^3 V^3 \quad , \text{ dB} \quad (11)$$

3. SIMULATION RESULTS AND PERFORMANCE ANALYSIS

The recent developments of low driving voltage and high modulation efficiency of EAMs over wide range of the affecting operating parameters have been deeply investigated as shown in Table 2.

Table 2: Proposed operating parameters for electro-absorption modulators

Parameter	Definition	Value and unit
T=T ₀	Ambient temperature=room temperature	300 K
L	Modulator length	300 μm
t	Modulator thickness	25 μm
P	Input light power	0.1 Watt—0.5 Watt
λ	Operating signal wavelength	1.3 μm—1.55 μm
	Electrooptic coefficient for AS ₂ S ₃	35 Pm/volt
	Electrooptic coefficient for Ge	48 Pm/volt
	Electrooptic coefficient for Si	23 Pm/volt
Γ	Confinement factor	0.9

V	Applied bias voltage	1 Volt—10 Volt
q	Electron charge	$1.6 \times 10^{-19} \text{C}$
c	Speed of light	$3 \times 10^8 \text{ m/sec}$
h	Planck's constant	$6.02 \times 10^{-34} \text{ J.sec}$

Based on the model equations analysis, assumed set of the operating parameters, and the set of the series of the Figs. (1-11), the following facts are assured:

- i) Figs. (1, 2) have assured that effective relative refractive index difference increases with increasing applied bias voltage and decreasing operating optical signal wavelength for different materials under study. We have observed that the Ge material has presented the highest effective relative refractive index difference compared to other materials.
- ii) As shown in Figs. (3, 4) have proved that modulation photo current increases with increasing both input light power and operating optical signal wavelength for different materials under considerations. We have indicated that the As_2S_3 material has presented the highest modulation photo current compared to other materials.

iii) Figs. (5-7) have demonstrated that modulator transmission increases with increasing operating optical signal wavelength and decreasing applied bias voltage for different materials under study. We have also observed that the As_2S_3 material has presented the highest modulator transmission compared to other materials.

iv) Fig. 8 has indicated that modulator insertion loss decreases with increasing operating optical signal wavelength for different materials under considerations. As well as we have indicated that the As_2S_3 material has presented the lowest insertion loss compared to other materials.

v) Figs. (9-11) have assured that modulator extinction ratio increases with increasing both operating optical signal wavelength and applied bias voltage for different materials under study. Moreover we have also observed that the As_2S_3 material has presented the highest extinction ratio compared to other materials.

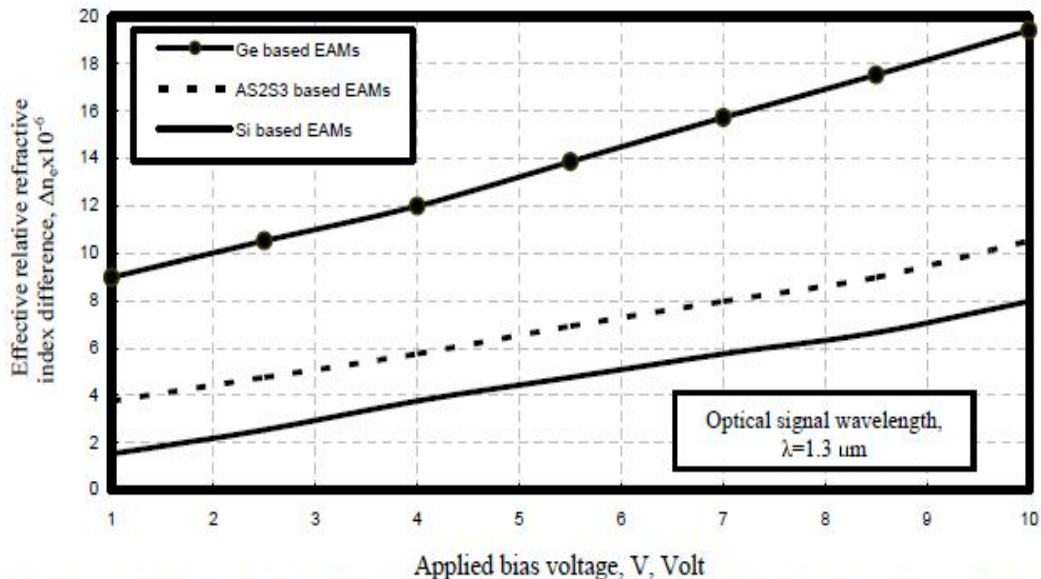


Fig. 1. Effective relative refractive index difference in relation to applied bias voltage and operating optical signal wavelength at the assumed set of the operating parameters.

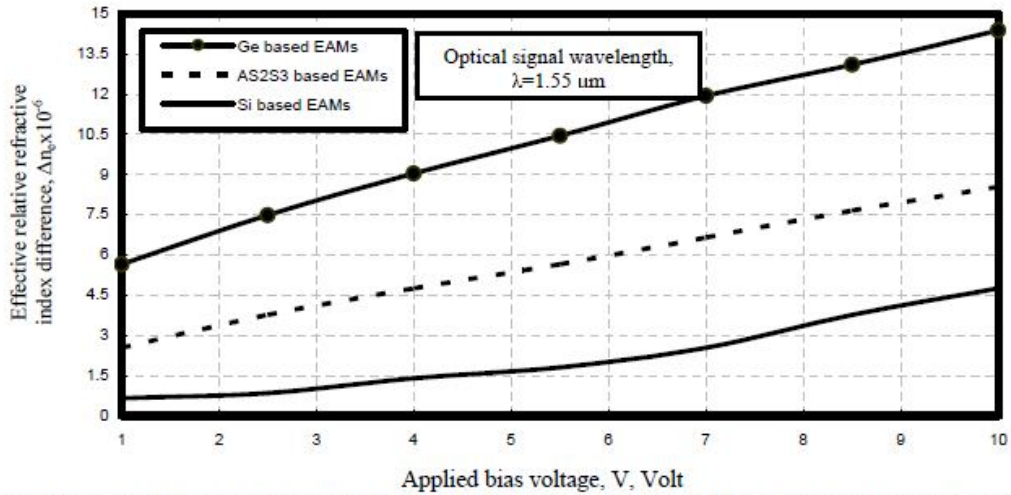


Fig. 2. Effective relative refractive index difference in relation to applied bias voltage and operating optical signal wavelength at the assumed set of the operating parameters.

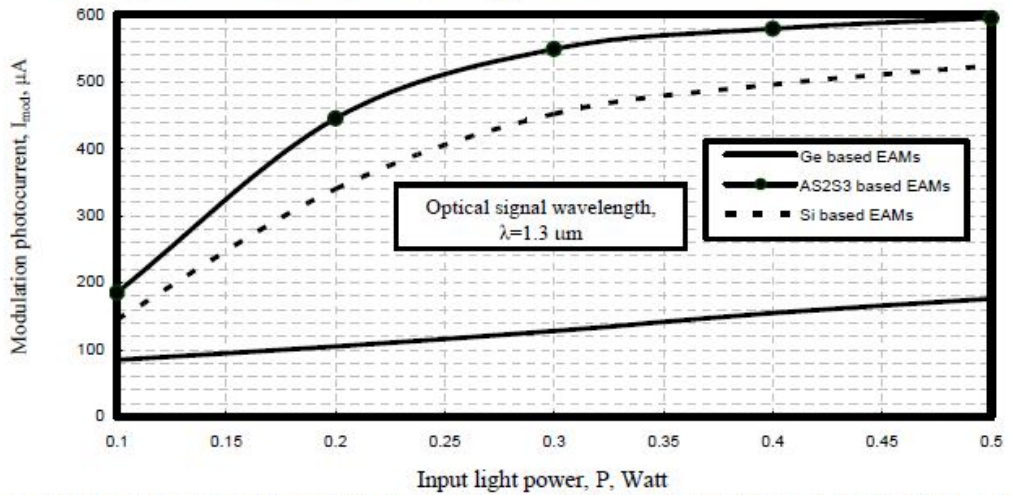


Fig. 3. Modulation photo current in relation to input light power and operating optical signal wavelength at the assumed set of the operating parameters.

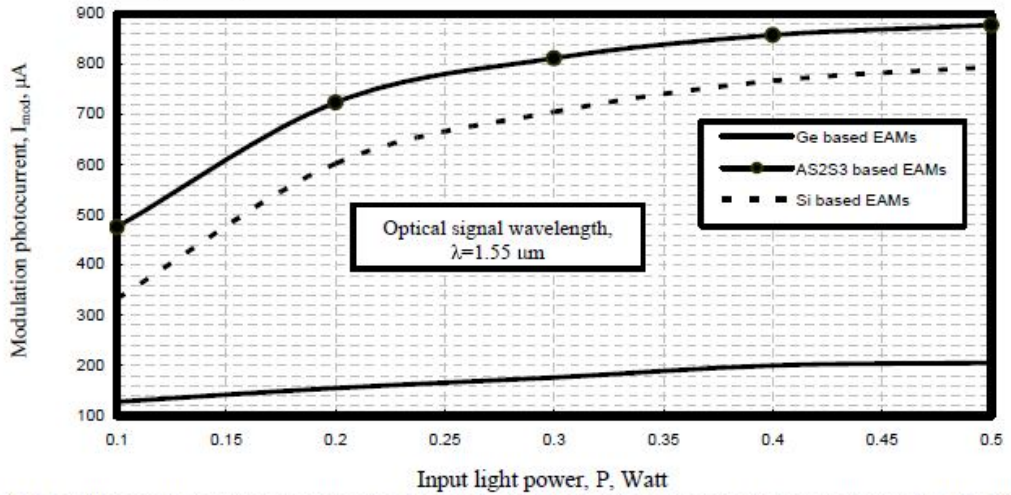


Fig. 4. Modulation photo current in relation to input light power and operating optical signal wavelength at the assumed set of the operating parameters.

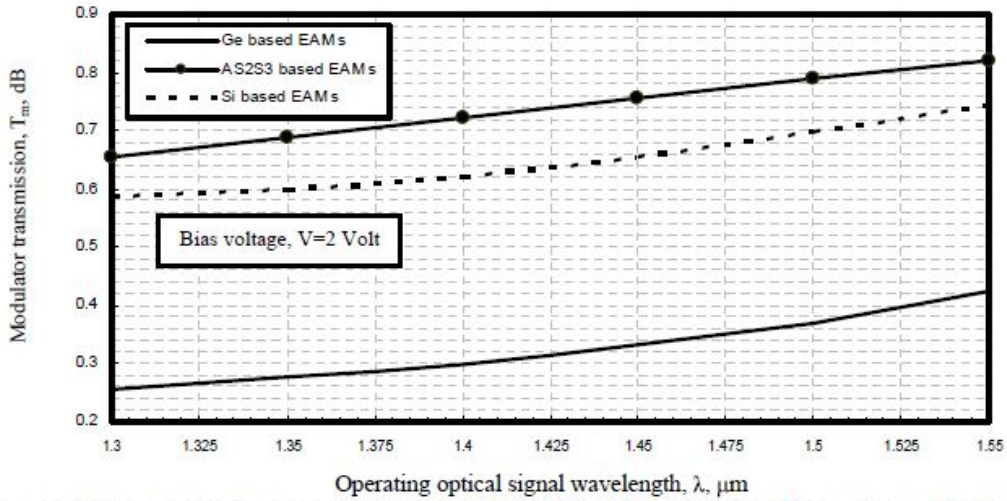


Fig. 5. Modulator transmission in relation to operating optical signal wavelength and bias voltage at the assumed set of the operating parameters.

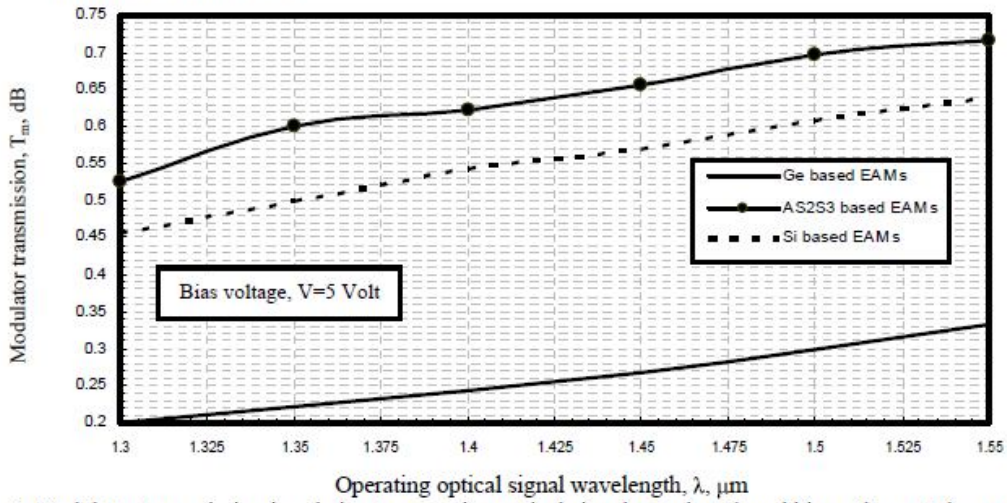


Fig. 6. Modulator transmission in relation to operating optical signal wavelength and bias voltage at the assumed set of the operating parameters.

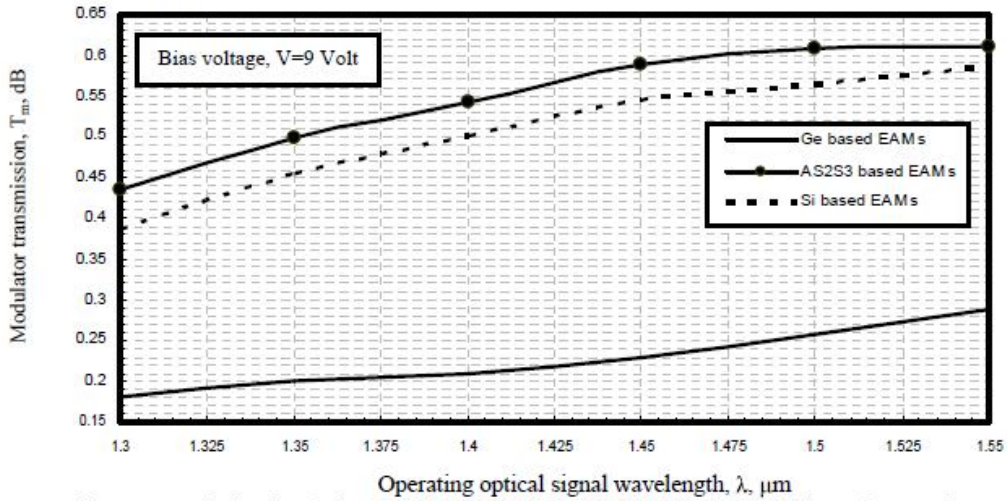


Fig. 7. Modulator transmission in relation to operating optical signal wavelength and bias voltage at the assumed set of the operating parameters.

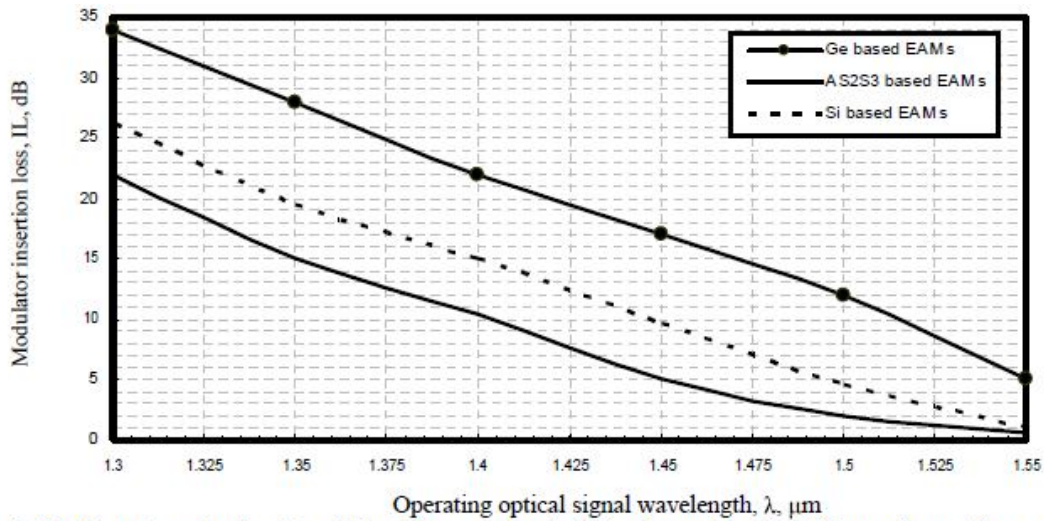


Fig. 8. Modulator insertion loss in relation to operating optical signal wavelength and bias voltage at the assumed set of the operating parameters.

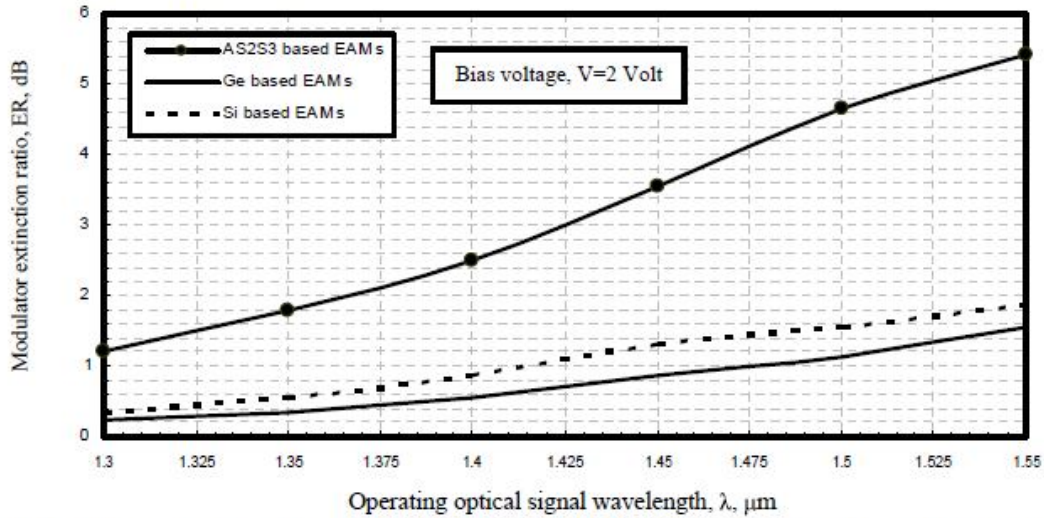


Fig. 9. Modulator extinction ratio in relation to operating optical signal wavelength and bias voltage at the assumed set of the operating parameters.

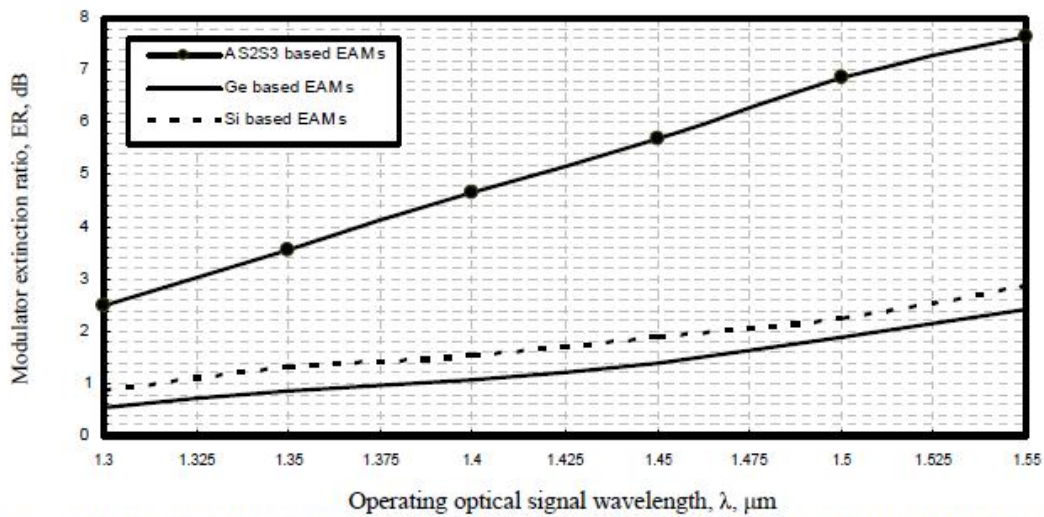


Fig. 10. Modulator extinction ratio in relation to operating optical signal wavelength and bias voltage at the assumed set of the operating parameters.

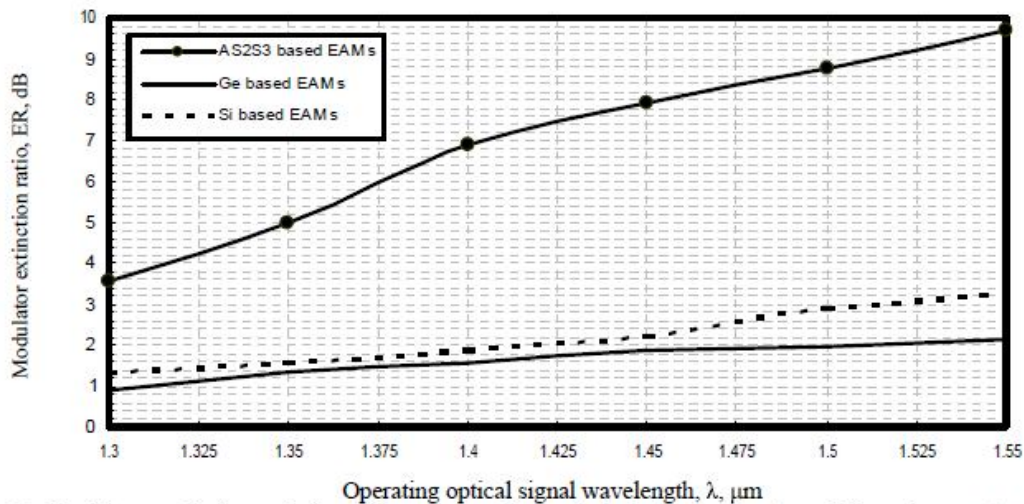


Fig. 11. Modulator extinction ratio in relation to operating optical signal wavelength and bias voltage at the assumed set of the operating parameters.

4. CONCLUSION

Traveling wave electro absorption modulators using the Si, Ge, and As₂S₃ material system have been demonstrated. For a 300 μm long device, a extinction ratio with arrange of 2-10 dB, insertion loss with the range of 5-30 dB, and modulator transmission with the range of 0.2-0.9 dB are achieved for the selected materials based EAMs under considerations. It is indicated that As₂S₃ has presented the highest modulation photo current, transmission, and the extinction ratio, and the lowest insertion loss compared to other materials under study and under the same operating conditions. These results show that with good design, electro-absorption modulators can overcome the insertion loss limitation and obtain higher speed, lower driving voltage and larger extinction ratio for optical fiber communication applications with using As₂S₃ based EAMs.

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